



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	<i>Baer et al.</i>)	Group No.:	1763
Serial No.:	10/675,697)	Examiner:	Arancibia
Filed:	09/30/2003)	Docket No.:	HSJ9-2003-0032US1

For: "METHOD OF FORMING A READ SENSOR USING PHOTORESIST
STRUCTURES WITHOUT UNDERCUTS WHICH ARE REMOVED
USING CHEMICAL-MECHANICAL POLISHING (CMP) LIFT-OFF
PROCESSES"

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

AMENDMENT AND REQUEST FOR RECONSIDERATION

The Applicants respectfully submit this Amendment And Request for Reconsideration for entry into the present application in response to the Office Action mailed on 21 March 2006.